

Title (en)

PROCESSOR FOR PHOTOSENSITIVE MATERIAL WITH LAMINAR FLUID FLOW WICK

Publication

EP 0491182 A3 19930217 (DE)

Application

EP 91119964 A 19911122

Priority

US 62805290 A 19901217

Abstract (en)

[origin: US5093678A] A processor for photosensitive material provides a processing solution to a processing chamber while the photosensitive material is advanced through the chamber. The processing solution is drained from the chamber and passes through a chute as it is returned to a sump for recirculation to the processing chamber. A laminar fluid flow wick located in the chute avoids air entrapment that would be caused by fluid freely flowing through the chute.

IPC 1-7

G03D 5/00

IPC 8 full level

G03D 3/00 (2006.01); **G03D 3/08** (2006.01); **G03D 5/00** (2006.01); **G03D 5/04** (2006.01)

CPC (source: EP US)

G03D 5/003 (2013.01 - EP US); **G03D 5/04** (2013.01 - EP US)

Citation (search report)

- [AP] US 4994840 A 19910219 - HALL DOUGLAS O [US], et al
- [A] DE 3623452 A1 19880128 - THEILEMANN RETHETO FILMTECH [DE]
- [A] US 1928235 A 19330926 - TAYLOR LOREN E

Designated contracting state (EPC)

DE FR GB IT

DOCDB simple family (publication)

US 5093678 A 19920303; EP 0491182 A2 19920624; EP 0491182 A3 19930217; JP H04294349 A 19921019

DOCDB simple family (application)

US 62805290 A 19901217; EP 91119964 A 19911122; JP 33349791 A 19911217